
**Microbeam analysis — Guidelines
for misorientation analysis to assess
mechanical damage of austenitic
stainless steel by electron backscatter
diffraction (EBSD)**

*Analyse par microfaisceaux — Lignes directrices relatives à
l'analyse des défauts d'orientation pour l'évaluation des dommages
mécaniques de l'acier inoxydable austénitique par diffraction
d'électrons rétrodiffusés (EBSD)*



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Published in Switzerland

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Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular, the different approval criteria needed for the different types of ISO documents should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see www.iso.org/directives).

Attention is drawn to the possibility that some of the elements of this document may be the subject of patent rights. ISO shall not be held responsible for identifying any or all such patent rights. Details of any patent rights identified during the development of the document will be in the Introduction and/or on the ISO list of patent declarations received (see www.iso.org/patents).

Any trade name used in this document is information given for the convenience of users and does not constitute an endorsement.

For an explanation of the voluntary nature of standards, the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the World Trade Organization (WTO) principles in the Technical Barriers to Trade (TBT), see www.iso.org/iso/foreword.html.

This document was prepared by Technical Committee ISO/TC 202, *Microbeam analysis*.

Any feedback or questions on this document should be directed to the user's national standards body. A complete listing of these bodies can be found at www.iso.org/members.html.

Introduction

Mechanical damage such as creep or fatigue, in engineering materials can be assessed by misorientation analysis using electron backscatter diffraction (EBSD) technique. The EBSD technique measures crystal orientation of sample surface by indexing EBSD patterns which are acquired by scanning its surface with electron beam in a scanning electron microscope (SEM). It can give orientation maps and misorientation maps. To determine the degree of damage induced in the materials, the misorientations calculated from the mapping data are qualified by various parameters such as the local misorientation, which is an averaged misorientation between neighbouring measurement points, and intra-grain misorientations, which is an averaged misorientation between the reference orientation assigned to each crystal grain and measurement points inside the grain. These misorientation parameters correlate well with the degree of mechanical damage caused by deformation, fatigue and/or creep. Therefore, the magnitude of the material damage can be estimated using the correlation curve which represents the relationship between the misorientation parameters and the degree of the damage (hereafter called correlation curve).

In the EBSD measurement, the crystal orientation is identified through electron beam illumination to the material surface, acquisition of the EBSD pattern by an image detector, and then crystal orientation identification by indexing of the EBSD patterns. It was shown that the point to point accuracy of the crystal orientation measurement is about $0,05^\circ$ to $0,5^\circ$. The misorientation parameters vary depending on SEM conditions, observation conditions, EBSD pattern acquisition conditions and crystal orientation identification conditions. Several measurement parameters are determined for calculating the misorientation parameters. In particular, the local misorientation greatly depends on the distance between the measurement points (step size). Furthermore, the accuracy of the crystal orientation measurement and the definition of the misorientation parameters may depend on the hardware and software used for the measurement and analysis. There are several vendors of commercial EBSD measurement and analysis systems. The correlation curve obtained for a certain condition using a certain measurement system is not always comparable with other master curve obtained with different conditions or systems. Therefore, it is necessary to have a standard to measure comparable master curves to show the degree of mechanical damage by using any EBSD systems.

This document describes measurement procedures and conditions and definitions of misorientation parameters independent on the measurement system in order to assess damage of austenitic stainless steel precisely.

Microbeam analysis — Guidelines for misorientation analysis to assess mechanical damage of austenitic stainless steel by electron backscatter diffraction (EBSD)

1 Scope

This document describes the guidelines for misorientation analysis to assess mechanical damage such as fatigue and creep induced by plastic and/or creep deformation for metallic materials by using electron backscatter diffraction (EBSD) technique. This international standard defines misorientation parameters and specifies measurement conditions for such mechanical damage assessment. This document is recommended to evaluate mechanical damage of austenitic stainless steel, which is widely used for various components of power plants and other facilities.

In this document, the mechanical damage refers to the damage which causes the fracture of structural materials due to external overload, fatigue and creep; excepting the chemical and thermal damages themselves.

2 Normative references

The following documents are referred to in the text in such a way that some or all of their content constitutes requirements of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

ISO 24173:2009, *Microbeam analysis — Guidelines for orientation measurement using electron backscatter diffraction*

3 Terms and definitions

For the purposes of this document, the following terms and definitions apply.

ISO and IEC maintain terminology databases for use in standardization at the following addresses:

- ISO Online browsing platform: available at <https://www.iso.org/obp>
- IEC Electropedia: available at <https://www.electropedia.org/>

3.1

area averaged intra-grain misorientation

average of intra grain misorientation of all pixels in the measurement area

3.2

area averaged local misorientation

average of local misorientation of all pixels in the measurement area

3.3

blank point

non-indexed point (pixel) due to insufficient quality of the EBSD pattern

Note 1 to entry: This can occur for a variety of reasons, such as insufficient specimen surface condition, dust or contamination on the specimen surface, overlapping patterns at the grain boundary, a poor-quality pattern due to the effects of strain, or if the pattern is from an unanticipated phase.

Note 2 to entry: See ISO 13067:2020, 3.4.2 for definition of non-indexing.